# Investigation of Wide Bandgap Materials for Cold Electron Emission

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# **Outline**

- I. Cold Cathode Development Challenges and Issues
- II. Wide Bandgap Emitter Materials
- III. Technical Approach
  - Surface Characterization
  - Transport and Emission Studies
  - Injection Models
- IV. Novel Materials
- V. Conclusions

# **Challenges: Cold Cathode Technology**

#### Innovative Cold Electron Sources Must Be Developed That Provide:

- · High current density J
- Uniform emission
- Robust emission
- Low voltage operation
- Emission modulation

High-performance Cold Cathodes Are Needed to Enable Next-generation Vacuum Electron Devices with:

- Higher power
- More compact size
- Increased efficiency
- Longer life

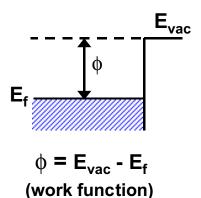
# **Emission Process in Cathode Materials**

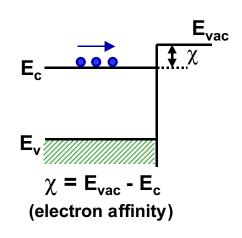
# **Emission Process**

- Escape across surface barrier
- Electron supply mechanism

#### Metal

## **Semiconductor or Insulator**





<u>Material</u>	Emission type	Surface barrier	Electron supply
metal	thermionic	ф	conduction e-s
	field emission	tunneling	conduction e-s
non-metal	field emission	tunneling	valence e-s
	cold (low field)	χ	conduction e-s

⇒ need low or negative electron affinity (NEA)

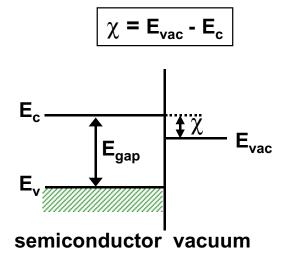
# Wide Bandgap Materials

## **Materials**

$$\begin{array}{ll} \text{Diamond} & \text{E}_{\text{gap}} = 5.5 \text{ eV} \\ \text{Al}_{x}\text{Ga}_{1\text{-}x}\text{N} & 3.4 \leq \text{E}_{\text{gap}} \leq 6.2 \text{ eV} \\ (0 \leq x \leq 1) & \end{array}$$

## **NEA Surface Properties**

Diamond 
$$\chi < 0$$
  
Al<sub>x</sub>Ga<sub>1-x</sub>N  $\chi < 0$  for x > 0.75



## **Electron Transport Properties**

• High current density:  $J \sim 10^3 - 10^5 \text{ A/cm}^2$ 

• High electron mobilities:  $\mu \sim 1600 \text{ cm}^2/\text{V-s}$  (diamond)

 $\sim$  1200 cm<sup>2</sup>/V-s (GaN)

High breakdown fields: E ~ 8 x 10<sup>6</sup> V/cm (diamond)

 $\sim 3 \times 10^6 \text{ V/cm (GaN)}$ 

# **Opportunities in Cold Cathode Development**

# **Materials**

Wide Bandap Materials: Diamond, III-Nitrides

- → high-electron-density transport
- → small or negligible surface barrier

# **Growth / Fabrication Capabilities**

- Molecular Beam Epitaxy (MBE)
- Chemical Vapor Deposition (CVD)
- Doping Control
- Heterostructures and Multi-layer structures

# **Cold Emission Process**

The development of wide bandgap cold emitter materials must address the 3 steps involved in the emission process:

**Injection:** Develop injection mechanism to maintain electron supply

in conduction band

Transport: Determine influence of material properties on the intensity

and energy distribution of transmitted electrons

**Emission:** Identify stable low or negative electron affinity surfaces

and characterize emitted electron distribution

# **Approach: Cold Cathode Development**

#### 1) Evaluate Transport and Emission Processes

If electrons are present in the conduction band:

- How efficient is emission at NEA surface?
- What are the electron emission characteristics?
- How do the bulk and surface properties affect the emission?
- 2) Develop Cathode Structures to Supply Conduction Electrons
  - How are electrons injected into the conduction band?
  - How is electron supply maintained?

# **Studies: Surface and Transport Properties**

```
Surface Studies
                     (Diamond: B. Pate-WSU, R. Nemanich-NCSU, J. Robertson-Cambridge, )
                     (III-Nitride: A. Kahn-Princeton, R. Nemanich-NCSU, V. Bermudez-NRL, )
 material
                    χ (eV)
                                         stability
 bare C
                    ~0.5
                                     heat to T > 1000 °C to clean
 H/C
                  - (1.0-2.0)
                                     stable to T ~ 1000°C
 Bare GaN
                    +3.3
                                     N-sputter & anneal (1100°C) to clean
                                     very reactive
                  < 0 \text{ to } +1.9
 Bare AIN
```

Electronic Studies (P. Cutler-PSU, P. Mumford-AF-WL, )

-0.7

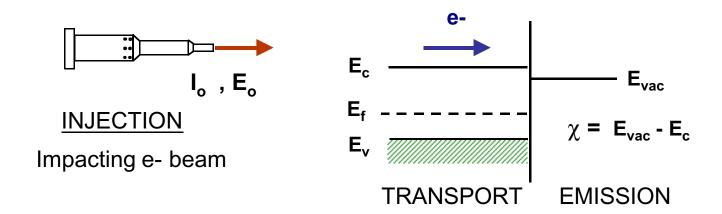
Cs

Diamond: Ballistic electron transport through conduction band

Transport through defect states or bands also possible

III-Nitrides: Ballistic transport through conduction band

# NRL Studies: Transport and Emission



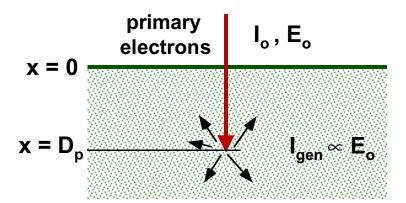
- Injection of high-energy electrons into material using e- gun
- Transport and Emission of low-energy electrons at NEA surface
- Measurements: Energy distribution curves
   Secondary yield curves

## **Techniques**

- Secondary electron emission spectroscopy
- Transmission electron spectroscopy

# **Secondary Emission Process In Wide Bandgap Material**

## **Generation of secondary electrons**

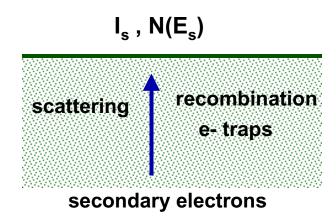


As E<sub>o</sub> Increases:

Penetration Depth Increases

**Generation Depth Increases Generated Current Increases** 

Transport to and emission at surface

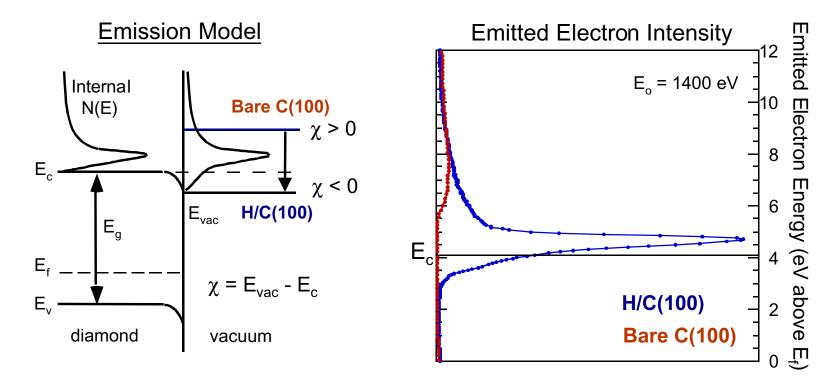


**Transport Process** 



Inelastic Scattering  $\rightarrow$  Energy Loss Recombination/Traps  $\rightarrow$  Intensity Loss

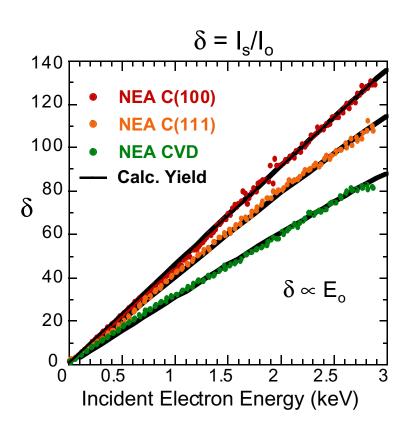
# **Low-Energy Electron Emission From Diamond**



- Emitted energy distribution is sensitive to  $\chi$
- Electron distribution dominated by low-energy electrons
   ⇒ FWHM ~ 0.5 eV, <KE> ~ 0.5 eV

Cold low-e nergy electrons are emitted efficiently at NEA surface

# Efficient Transport of Low-Energy Electrons in Diamond



- Extremely high yields
  - $\rightarrow$   $\delta$  ~ 90 130 !!
- $\delta$  increases with increasing E<sub>o</sub>

$$\Rightarrow$$
 D<sub>esc</sub> >> 0.13  $\mu$ m

Secondary yield calculations:\*

$$\Rightarrow$$
 D<sub>esc</sub> ~ 1 - 5  $\mu$ m

\* Martinelli and Fisher, Proc. IEEE 62, 1339 (1974)

Low-energy electrons have long escape depths in diamond samples

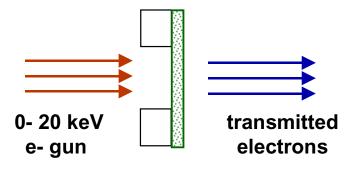
⇒ Examine transport process more directly in transmission studies

# **Electron Transmission Studies**

## **Experimental Approach**

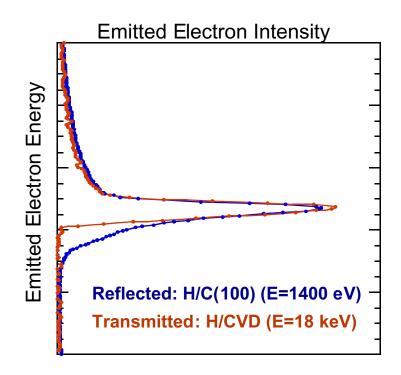
CVD diamond film on Si substrate\*

⇒ Si etched to create diamond window



 $\begin{array}{ccc} \underline{Thickness} & \underline{B\text{-doping}} \\ 1 - 10 \ \mu m & low \rightarrow high \end{array}$ 

- Determine effect of dopants on transport
- Determine escape depth of secondary electrons



#### **Initial Studies**

Energy distribution is nearly identical in reflection and transmission measurements

⇒ Need to understand factors that limit transmitted *current* 

<sup>\*</sup> J. Butler and P. Pehrsson, NRL

# **Approach: Cold Cathode Development**

- 1. Evaluate Transport and Emission Processes
  - Low-energy electrons are emitted very efficiently at NEA surfaces
  - Energy distribution is sharply peaked at very low KE
  - Low-energy electrons have long escape depths in diamond
    - → Influence of bulk properties is under investigation
    - → Emission at III-nitride surfaces is under investigation
- 2. Develop Cathode Structures to Supply Conduction Electrons
  - How are electrons injected into the conduction band?
  - How is electron supply maintained?

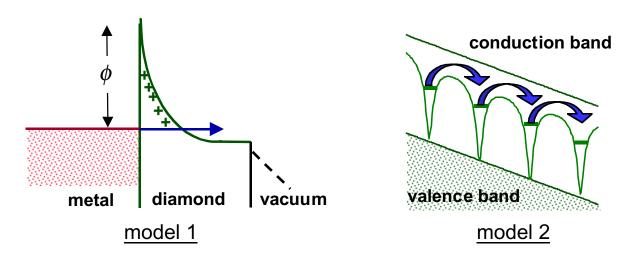
Various Injection Models Under Theoretical & Experimental Investigation

# Internal Field Emission Model in Diamond

Main Barrier to Emission Is at Back Contact

**Approach**: Dope with N impurities (deep donor levels)

→ Depletion layer created at back contact that produces band bending and narrowing of the barrier

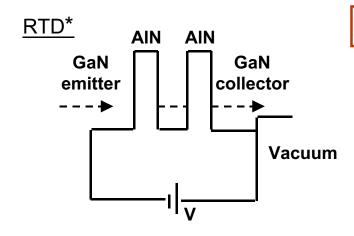


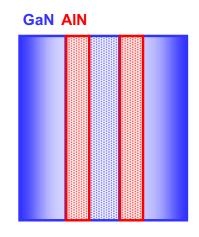
## **Transport Under Applied Field**

model 1: electrons tunnel through to conduction band (M. Geis, MIT-LL)

model 2: electrons hop through gap via impurity or defect levels (A. Gohl)

# Resonant Tunneling Diode (RTD) Emitter





RTD based on AIN/GaN/AIN quantum well

#### **Tunneling Transport Characteristics**

- narrow energy distribution
- narrow momentum distribution
- $J_{max} \sim 300 \text{ kA/cm}^2$  (reported for InAs/AISb)

#### **Predicted Emission Characteristics**

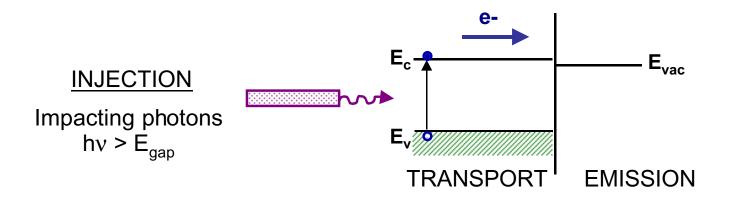
- monoenergetic beam
- highly-collimated beam
- beam modulated by V

#### **Key Issues**

- Current density through AlGaN RTD
- Effect of impurities and defects
- Small surface barrier

<sup>\*</sup>S. Krishnamurthy, SRI International

# **Photo-injection Mechanism**



III-Nitrides are *direct* bandgap materials ⇒ Opto-Electronic Devices

## **Advantages of external photon source**

- Emitter structure is less complex, easier to optimize
- Laser provides injection and modulation capabilities

### **Disadvantages of external photon source**

- Cathode-laser system is cumbersome
- Higher input power demands

*Internal* photon source possible ⇒ Complex heterostructure design

# Status: Wide Bandgap Emitter Materials

# Material Issues ⇒ Key to Successful Cold Cathode Development

#### **Diamond: Material Challenges**

- n-type doping shallow donor
  - → Reduced Schottky barriers or ohmic back contacts
- Reproducible high-quality CVD diamond growth

#### **III-Nitrides: Material Challenges**

- Surface preparation for low or negative  $\chi$ 
  - → Investigate electronic structure of AIN and AIGaN alloy surfaces prepared under various conditions
- Reduce defects/dislocations
  - → Study scattering mechanisms and transport in specific materials and device structures
- Improved control of doping (p-type, n-type contaminants)

# **Novel Emitter Materials**

Other Carbon Materials: Diamond-like Carbon

**Nano-crystalline Diamond** 

**Carbon Nanotubes** 

- √ Harsher growth conditions are allowed.
- $\sqrt{\phantom{a}}$  Cheaper fabrication processes can be used
- $\sqrt{\phantom{a}}$  Novel materials are produced

But ... material properties may not be well understood

- → Emission model?
- → Uniformity?
- → Reproducibility?

# **Amorphous and Nano-Crystalline Carbon**

#### **Diamond-like Carbon (DLC)**

Amorphous semiconductor with sp³ (diamond) and sp² (graphite) bonds  $E_{gap} \sim 1$  - 4 eV  $(\chi \downarrow as E_{gap} \uparrow)$ ;  $\phi \sim 3.5$  - 4.0 eV High density of defects

## Nano-grained CVD Diamond

Nano-crystalline grains  $\sim 50\text{-}100 \text{ nm}$ High density of conducting grain boundaries Graphitic phase at boundaries with  $\phi = 4.7 \text{ eV}$ 

#### Main Emission Barrier Is at Front Surface → Need to Tunnel Across Barrier

## Very high fields can be created at C surfaces due to:

- nm-size surface regions with different termination ⇒ High local fields
- High defect density causes short depletion width ⇒ High near-surface fields
- High breakdown fields in diamond-like material

DLC: Dope with N (shallow donor) to decrease  $\phi$ ; increase sp<sup>3</sup> content to decrease  $\chi$ 

CVD: Field enhancement at conducting grain boundaries, surface roughness

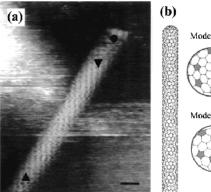
# **Carbon Nanotubes**

## Nanotubes: sp²-bonded rolls of graphite

- Similar electronic structure to DLC
- High-density arrays of aligned nanotubes

#### Field Emission Studies (W. Zhu, Lucent)

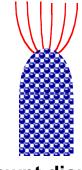
Best emission from single-walled nanotubes (swnt)  $J_{max} \sim 1 - 5 \text{ A/cm}^2$  Emission site density  $\sim 10^4 \text{ cm}^{-2}$ 





#### **Cathode Issues**

- Emission due to small tube size
  - ⇒ Characterize emission as function of tube size
  - ⇒ Determine optimum array structure
- Low adsorbate sensitivity
  - ⇒ Determine effect of tube size, structure on reactivity
- Extremely rigid, strong and possibly self-healing
  - ⇒ Determine robustness in sputtering environment



swnt diam. ~ 1-5 nm

# **Future Prospects for Cathode Development**

Steady advances in materials growth, fabrication, and design are expected due to:

- powerful new characterization tools
- precision instrumentation for controlled growth
- deeper understanding of material properties

#### **Near-term Prospects**

Improvements in the quality and control of wide bandgap materials will enable the development of high-performance cold cathodes for specific device applications and operating environments

## **Long-term Prospects**

Potential for new classes of materials, new structures, and new emission mechanisms